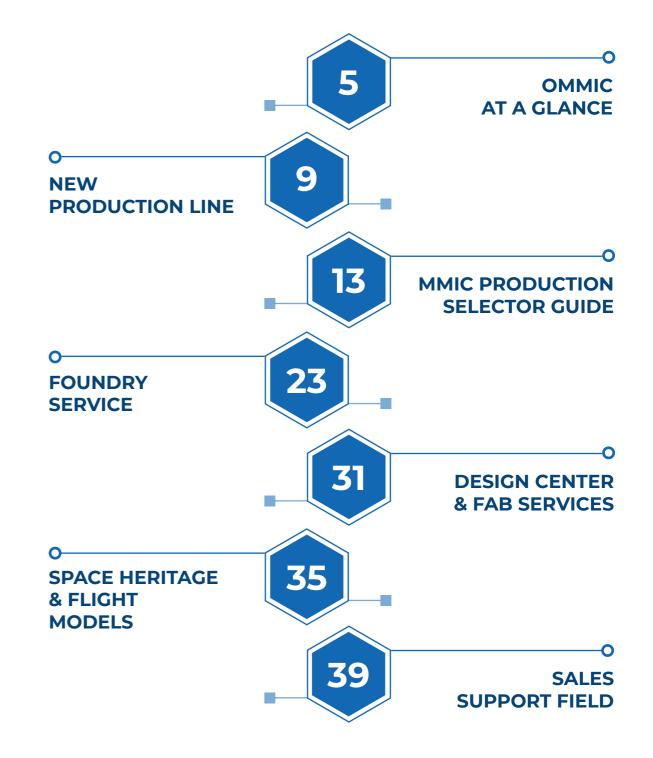




represented by Tom Terlizzi GM Systems 27 Kim Place Kings Park, N.Y. 516-807-9488 cell 631-269-3820 Office terlizzi@gmsystems.com www.gmsystems.com



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FOREWORD

« OMMIC is a pioneer and a leader in the III/V domain, in particular in GaN and GaAs semiconductor technologies. With the release of its new 6-inch production line, OMMIC has positioned itself as French industrial leader in the development of the European telecommunications. Its current technologies provides solutions for the 5G base station market at 28 and 40 GHz, as much for the backhaul part of the network. Indeed, OMMIC's GaN processes can be used at frequencies above 30 GHz with power output that has never been reached before in the industry. In addition, OMMIC is continuously investing in research and development to help its customers built new technologies.

With this unique line in Europe, OMMIC affirm its ambition to strenghten its leadership in the market with ever-increasing production volumes.»







OMMIC AT A GLANCE

A LEADING SUPPLIER

OMMIC, based in France, near Paris, is a leading supplier of Epitaxy, Foundry Services and MMICs based around the most advanced III-V processes.

Formerly Philips Semiconductor, OMMIC is exploiting more than 40 years background in III-V Materials, Design and Processing. Thanks to its innovative solutions, OMMIC enables its customers to be leaders in a more and more demanding market place.

OMMIC operates in a highly competitive global market and must be competitive and responsive. OMMIC has been ISO 9001 certified since 1994 and ISO 14001 since 2002. This sustainable commitment is fully supported by its quality management system.



We have been working in collaboration with ESA for more than 20 years. ESA has already evaluated 3 OMMIC processes : EDO2AH, D01PH and D01MH. These 3 processes being maintained on ESA EPPL list. Two additional processes (including the D01GH GaN/Si) are being evaluated for insertion in the EPPL.

STEPS OF PRODUCTION



Step 6: VISUAL INSPECTION OMMIC visual inspect 100% of the dies with commercial and space grade screening.

Step 4: TEST OMMIC test 100% of the dies it produces. This includes RF and DC tests.

Step 2: E-BEAM OMMIC uses E-Beam lithography to define gates as small as 40 nm.

Step 3 : PRODUCTION

OMMIC produces in France near Paris. The company has a 3-inch and 6-inch Fab line.

Step 1: EPITAXY OMMIC has 4 Epitaxy reactors and develops its own epi structure.

INDUSTRIAL SECTORS

OMMIC is supplying MMIC, Fondry Services and Epitaxial Wafers based on III-V (GaN, GaAs and InP) materials.

With its advanced technology, OMMIC has proven itself as a leader in its fiels, providing its customers with cutting edge performance in the **Telecommunication**, Space and Defense markets.



33 % OF OUR MARKET IS FOR THE HIGH-END SPACE MARKET

45 % OF OUR MARKET IS FOR COMMERCIAL APPLICATION INCLUDING THE **NEW** CELLULAR TELECOM MARKET





OF OUR MARKET IS FOR THE **HIGH-END DEFENSE MARKET**

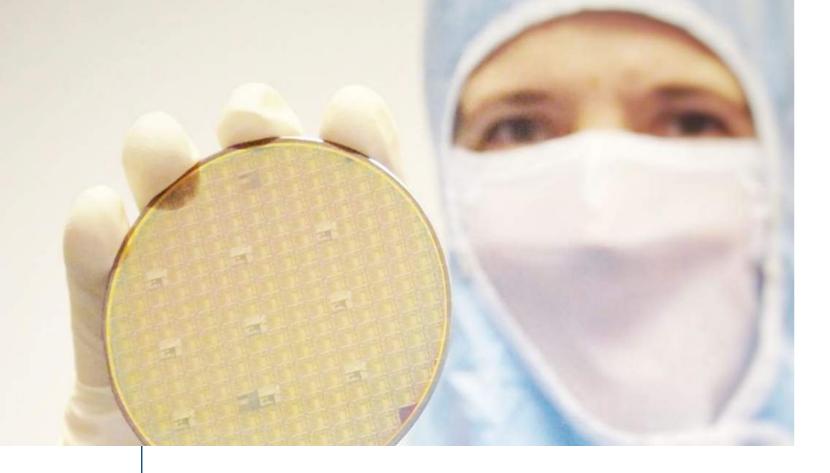
NEW PRODUCTION LINE











NEW PRODUCTION LINE

PRODUCTION

OMMIC was founded on January 1, 2000 by Philips, based on a track record of 40 years of cutting -edge research and development in the fields of III-V epitaxy and integrated circuits technologies. Today, we are an independant SME.

OMMIC consits of 5 main buildings with 1000m² of clean rooms of class 1000 and class 100 which are fully devoted to III-V IC development and fabrication.

Our wafers are delivered with electrical properties guaranteed by the mesurement of specific test modules added during the fabrication called PCM (Process Control Monitor). Our processes and our equipments are also followed with SPC (statistical process control).

TEST

Once the wafers are fabricated, **all dies are measured** with **DC** and **RF** metrics verified. This includes the bias levels, but also S-parameters, Power measurements, noise measurements, etc. This unsure OMMIC delivers only working dies with stunning performances.

Our experience in **microwaves** and mm-Waves tests and probe card's design, leads us to design complex tests procedures allowing testing the main performances and functionalities of our MMIC products in order to guarantee the delivery of know good dies. We open to our customers our RF-test capabilities and knowledge to design and conduct tests on their own prototypes, in order to help them to validate and improve their products.



INSPECTION

The **visual inspection process** plays an essential role in our manufacturing steps to ensure anomaly detection. We can therefore implement prompt corrective or preventive responses and verify the finaly quality of each die before sending them to our customers.

In order to do so, we perform prelimanary visual inspections at each critical step in the production line with sampling and a final visual inspection.

Two level of screening are available : Space grade for the highest reliability, and commercial grade for product with less stringent requirements.



STRATEGY & ROADMAP

Ommic strategy is articulated around GaN technology. With its wide bandgap and high electron mobility, GaN is a perfect candidate for emerging applications.

Our strategy includes :



Full Replacement of GaAs Solutions

OMMIC plans to fully replace its GaAs pHEMT solutions by its stateof-the-art GaN/Si technology, offering the best III-V RF solutions, complementary to Silicon RF solutions.



High-End Space Market

OMMIC continues to serve high-end high value-added space market, by taking advantage of its avant-garde Hi-Reliability process for consumer market.



New Cellular Telecom Market

OMMIC aims to enter cellular infrastructure market, especially 5G market with its cutting edge GaN/Si technology, bet suited for the 5G mmWave application.



High-End Defense Market

OMMIC continues to serve high-end high value-added military market, by taking advantage of its high-performance process for consumer market.

THE LATEST NEWS

D01GH

D01GH GaN/Si process is already available for OMMIC customer through open foundry service.

D006GH

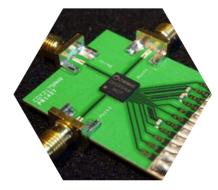
D006GH GaN/Si 60 nm process PDK is already available for dowload.

D004IH

D004IH is being developed, the advancement can be followed by looking at the Ultrawave H2020 public project.

MMIC PRODUCT SELECTOR GUIDE

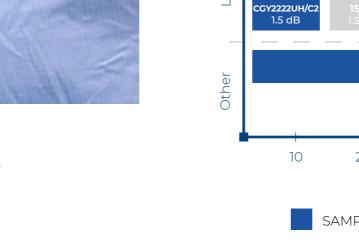
D01GH GaN/Si ■ INNOVATIVE GaN PRODUCTS LOW NOISE AMPLIFIERS POWER & WIDEBAND AMPLIFIERS CONTROL FUNCTIONS ■ MISCELLANEOUS







MMIC PRODUCT SELECTOR GUIDE



GaN LNA have been designed so that maximum input power is higher than 35 dBm. This is handy because, in most settings, no limitor is needed in front of the LNA.

LOW NOISE AM	PLIFIER						
PART	FRQNCY	GAIN	NF	OP1dB	VOLTAGE	CURRENT	PACKAGE
NUMBER	(GHz)	(dB)	(dB)	(dBm)	BIAS (V)	BIAS (mA)	& STATUS
CGY 2222 UH/C2	8 - 12	20	1.5	20	8	155	Die/Production
CGY 2231 UH	2 - 20	17	2.5	22	8	-	Die/Sampling
CGY 2250 UH/C1	26 - 34	20	1.6	27	8,5	90	Die/Production

POWER AMPLIFIER							
PART NUMBER	FRQNCY (GHz)	GAIN (dB)	Psat (dBm)	PAE (%)	VOLTAGE BIAS (V)	CURRENT BIAS @ Psat (A)	PACKAGE & STATUS
CGY2540UH CGY2631UH CGY2632UH CGY2650UH/C1 CGY2651UH/C1 CGY2652UH CGY2660UH	0.5 - 20 6 - 18 13 - 17 30 - 33.5 37 - 43 27 - 31 46 - 50	22 20 30 22 18 20 18	35 40 40 39 40 43 38	- 35 30 31 31 38 20	12 12 12 12 12 12 12 12	- 2 - 1.2 3.1 4 2.7	Die/Sampling Die/Sampling Die/Production Die/Production Die/Sampling Die/Sampling

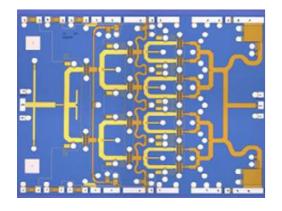
D01GH GaN/Si

D01GH FEATURE :

- Fmax: 160 GHz
- Gate length : 100 nm
- Ft:110 GHz
- Vbqd: 40 V

Main applications :

- High frequency PA 15 GHz to 50 GHz
- Instrumentation wide band amplifier DC 50 GHz
- Robust LNA (> 40 GHz) : up to 35 dBM Pin in CW

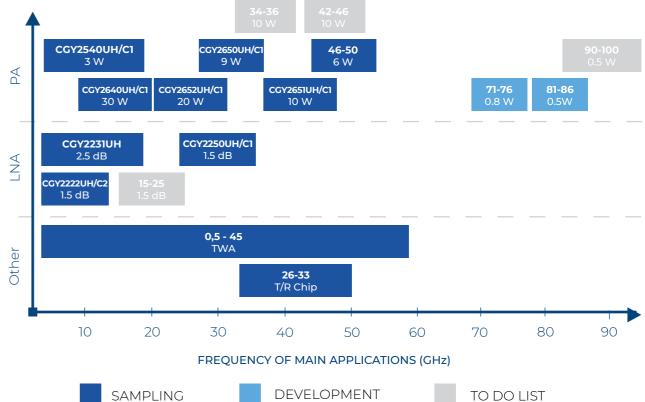


OMMIC's GaN has been engineered to reduce as much as possible traps in its process. The surface condition of GaN is being strictly monitored which is why, unlike most processes in production, OMMIC's D01GH has few-to-no measurable memory effect.

With D01GH, optimized digital predistortion technique can be used as much as **complex** modulation.

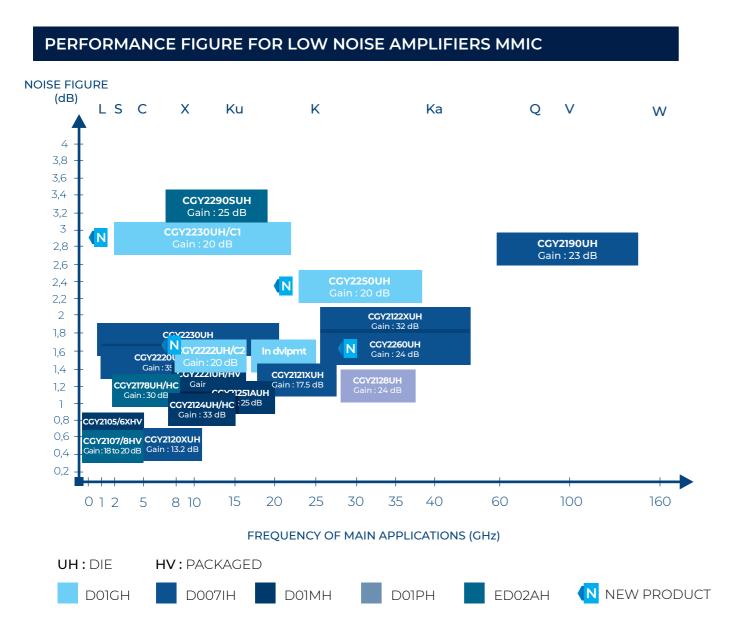
INNOVATIVE GaN PRODUCTS PORTFOLIO

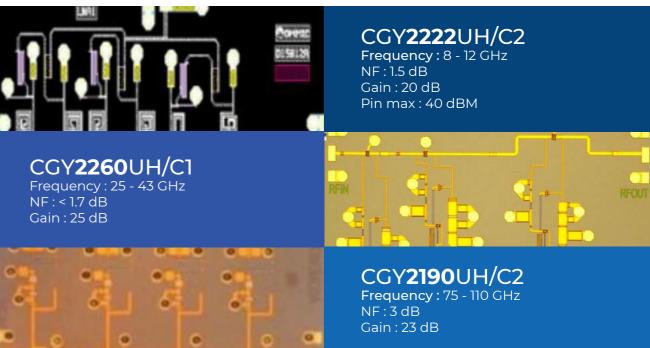
GaN products are being actively developped for emmerging applications : they are processed using D01GH GaN/Si technology which is 100% european source.



TWA								
PART NUMBER	FRQNCY (GHz)	GAIN (dB)	Psat (W)	COMPR POINT PIC		VOLTAGE BIAS (V)	CURRENT BIAS (A)	PACKAGE & STATUS
CGY 2550 UH/C1	0.6 - 40	16	2	19	9	18	91	Die/Production
T/R								
PART NUMBER	FRQNCY (GHz)	GAIN (dB)		tput R (dBm)	NF (dB)	VOLTAGE BIAS (V)	CURRENT BIAS (A)	PACKAGE & STATUS
CGY 2750 UH	26 - 34	20	3	5	3	12	0.45	Die/Sampling

LOW NOISE AMPLIFIERS PORTFOLIO





OMMIC Portfolio of MMICS, includes LNA from 500 MHz to 160 GHz for application such as telecommunication, passive imaging, radars and space.

LNA are manufactured using GaAs technology (ED02AH, D01PH, D01MH) that have been space qualified by ESA, or innovating technology : GaAs mHEMT for lower noises & higher frequencies of GaN HEMT (D01GH) for robust LNA.

PART NUMBER	FRQNCY (GHz)	GAIN (dB)	NF (dB)	OP1dB (dBm)	VOLTAGE BIAS (V)	CURRENT BIAS (mA)	PACKAGE & STATUS
CGY 2120 XUH/C1	5 - 7	13	0.5	12	1.0	50	Die/Production
CGY 2121 XUH/C1	18 - 26	18	1.5	5	0.8	60	Die/Production
CGY 2122 XUH/C2	25 - 43	32	1.5	1	1.1	30	Die/Production
CGY 2124 UH/C1	8 - 12	33	1.1	11	5.0	55	Die/Production
CGY 2125 AUH/C1	13 - 15	25	1.0	8	3.3	20	Die/Production
CGY 2128 UH/C2	24 - 34	24	1.3	11	3.5	47	Die/Production
CGY 2178 UH/C1	5 - 6	30	1.0	15	3.0	40	Die/Production
CGY 2190 UH/C2	75 - 110	23	3.0	1	1.0	33	Die/Production
CGY 2220 UH/C1	1 - 12	35	1.3	12	1.5	52	Die/Production
CGY 2221 HV/C1	7.5 - 13	17	1.7	17	5.0	82	QFN/Sampling
CGY 2221 UH/C1	7.5 - 13	17	1.6	17	5.0	82	Die/Production
CGY 2222 UH/C2	8 - 12	20	1.5	20	8.0	-	Die/Production
CGY 2230 UH/C1	1 - 18	35	1.5	12	1.5	50	Die/Production
CGY 2231 UH	2 - 20	17	2.5	22	8.0	-	Die/Sampling
CGY 2232 UH/C1	12 - 15	27	1.3	0	3.0	50	Die/Production
CGY 2250 UH/C1	26 - 34	20	1.6	27	8.0	90	Die / Production
CGY 2260 UH/C1	25 - 43	24	1.5	8	1.5	50	Die/Production
CGY 2272 UH	45 - 70	22	2.0	5	1.5	60	Die / Developemen
CGY 2290 SUH/C1	6 - 18	9	3.3	13	5.0	30	Die / Production

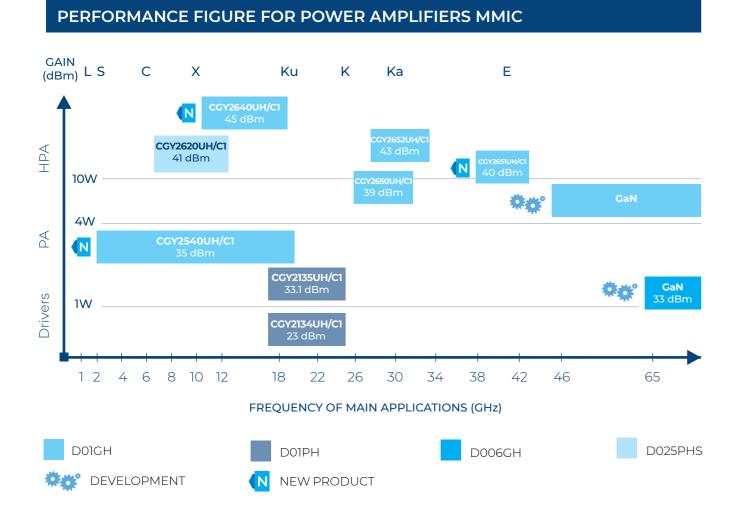
PERFORMANCE TABLE FOR ULTRA LOW NOISE AMPLIFIERS MMIC

PART NUMBER	FRQNCY (GHz)	GAIN (dB)	NF (dB)	OP1dB (dBm)	VOLTAGE BIAS (V)	CURRENT BIAS (mA)	PACKAGE & STATUS
CGY 2105 XHV	0.5 - 4	19	0.42	21	5	2 x 50	QFN 4×4 / Production
CGY 2106 XHV	0.1 - 3	19	0.45	19	5	2 x 50	QFN4x4/Production
CGY 2107 UH	0.5 - 6	24	0.60	22	5	2 x 50	QFN4x4/Production
CGY 2108 GS	0.5 - 6	21	0.60	22	5	2 x 50	Flight Model / Production
CGY 2108 HV	0.5 - 6	22	0.50	22	5	2 x 50	QFN 4 x 4 / Production

LNA written in blue are manufactured using GaN technology. They are therefore very robust and can handle more than 32 dBm input power in CW (> 40 dBM in pulse).

POWER & WIDEBAND AMPLIFIERS PORTFOLIO

OMMIC Portfolio of MMICS, includes Amplifiers from DC to 46 GHz for civil application such as Telecommunication, Instrumentation, Radars but also for Satcom and Military applicatons. PA were manufactured using GaAs technology (ED02AH, D01PH, D025PHS), that have been space qualified by ESA. New amplifiers are designed in GaN HEMT (D01GH) for outsanding performances.



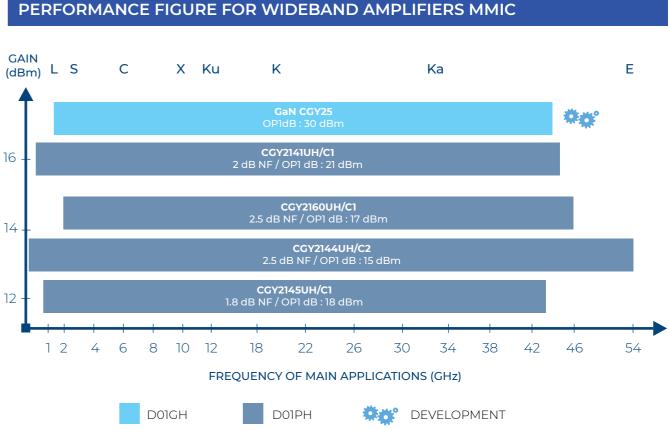
PERFORMANCE TABLE FOR POWER AMPLIFIERS MMIC

	PART NUMBER	FREQUENCY (GHz)	GAIN (dB)	Psat (dBm)	PAE @ Psat (%)	VOLTAGE BIAS (V)	CURRENT BIAS (A)	PACKAGE & STATUS
	CGY 2134 UH/C1	18 - 23	23	23	-	4.5	0.40	Die / Production
	CGY 2135 UH/C1	18 - 23	25	22	-	4.0	1.20	Die / Production
	CGY 2540 UH	0.5 - 20	22	35	-	12	-	Die / Sampling
	CGY 2620 UH/C1	8 - 11	25	42	-	9.0	3.25	Die / Production
Ν	CGY 2631 UH	6 - 18	20	40	35	12.0	2.0	Die / Sampling
Ν	CGY 2632 UH	13 - 17	30	40	30	12.0	-	Die / Sampling
Т	CGY 2650 UH/C1	29.5 - 33.5	22	39	30	12.0	1.20	Die / Production
	CGY 2651 UH/C1	40 - 46	20	34	35	12.0	3.20	Die / Production
Ν	CGY 2652 UH	27.5 - 31	-	-	30	12.0	-	Die / Sampling
Ν	CGY 2660 UH	46 - 50	18	38	20	12.0	2.70	Die / Sampling

OMMIC Power Amplifiers are dedicated to application such as radars, telecommunication and instrumentation. MMIC labeled in blue are using GaN technology.

The MMICs use gold bonding pads and backside metallization and are fully protected with Silicon Nitride passivation to get the highest level of reliability. D01PH technology has been evaluated for space applications and is on the European Preferred Parts List of the European Space Agency.

Wideband amplifiers are manufactured using OMMIC 130 nm gate length pHEMT Technology D01PH or 100 nm HEMT Technology D01GH.

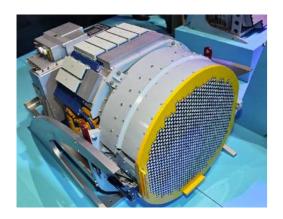


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	PERFORMANCE TABLE FOR WIDEBAND AMPLIFIERS MMIC									
	PART NUMBER	FRQNCY (GHz)	GAIN (dB)	Psat (W)	COMPRESSION POINT P1dB (dBm)	VOLTAGE BIAS (V)	CURRENT BIAS (A)	PACKAGE & STATUS		
	CGY 2141 UH/C1	DC - 46	16	0.20	21.0	5	195	Die/Production		
	CGY 2144 UH/C2	DC - 54	13	0.05	15.0	5	100	Die/Production		
	CGY 2145 UH/C1	0.5 - 45	13	0.10	18.0	5	85	Die/Production		
_	CGY 2160 UH/C1	1.5 - 47	15	0.08	19.0	5	103	Die/Production		
N	CGY 2550 UH	0.6 - 40	16	1.00	17.0	18	91	Die/Sampling		

MMIC labeled in **blue** are usign **GaN** technology. OMMIC Wideband Amplifiers are dedicated to application such as instrumentation, electronic warfare, 43 Gb/s OC-768 EAM Driver.

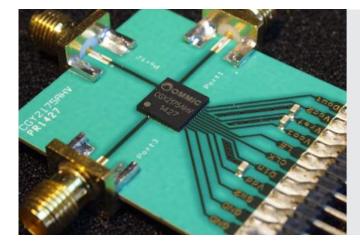
CONTROL FUNCTIONS ADVANTAGES & PORTFOLIO



OMMIC Portfolio includes Corechip and control functions.

Corechips are based on the integration in a single die of Digital Phase Shifters, Digital Attenuators, LNA, MPA and Switches for phased array antenna applications. Phases and attenuations states are controlled through a Serial to Parallel interface on the die (SIPO) built with OMMIC's E/D technology.

OMMIC SIPO stands for Serial Input Parallel Output. With the SIPO, the number of bonding is greatly reduced and only three of them are needed to control a corechip.



Exemple : CGY215AHV/C1 (6-bit package C-band corechip)

Each phase and attenuation states are loaded in the shift register (at a clock (CLK) rate up to 100 MHz), then phase and attenuation configuration are changed after latch enable (LE) signal.

Phase shifter, Attenuators, LNA and MPA integrated into a single chip controlled through Serial CMOS TTL compatible access.

PERFORMANCE TABLE FOR CORECHIP (PS TOPOLOGY CTRL R PART FRQNCY CTRL NUMBER (GHz) BITS CGY**2170**YHV/C1 8 - 12 6 3 ports 31.5/ CGY**2170**YUH/C1 8 - 12 6 3 ports 31.5 / CGY**2170**XHV/C2 8 - 12 6 4 ports 31.5 / CGY**2170**XUH/C2 8 - 12 4 ports 31.5 / 6 CGY**2175**AHV/C1 4.5 - 6.5 6 3 ports 31.5/ CGY**2175**AUH/C1 4.5 - 6.5 3 ports 31.5/ 6 CGY**2330**UH/C1 12 - 15 6 2 ports 31.5 / CGY**2350**UH/C1 34 - 36 5 3 ports 31.5 / CGY**2351**UH/C1 26.5 - 30.5 6 2 ports 31.5/

Phase shifter + LNA integrated in one die for internet over satellites Rx phased array antenna application.

PART	FRQNCY	CTRL	TOPOLOGY	GAIN /	RMS PHASE	CTRL	PACKAGE
NUMBER	(GHz)	BITS		NOISE (dB)	ERROR (°)	INTERFACE (V)	& STATUS
CGY 2179 HV	10.7 - 12.75	4	2 ports	12/2	7.00	0/+5	QFN/Production
CGY 2179 UH	10.7 - 12.5	4	2 ports	12/2	7.00	0/+5	Die/Production

PERFORMANCE TABLE TRUE-TIME DELAY FUNCTIONS							
PART	FRQNCY	CTRL	MIN	-	INSERTION	CTRL	PACKAGE
NUMBER	(GHz)	BITS	DELAY (ps)		LOSS (dB)	INTERFACE (M)	& STATUS
CGY 2393 SUH/C1	6 - 18	5	10	310	6	0 / +4	Die/Production
CGY 2394 SUH/C1	6 - 18	1	330	310	6	0 / +4	Die/Production

PERFORMANCE TABLE FOR DIGITAL PHASE-SHIFTER FUNCTIONS							
PART	FRQNCY	CTRL	INSERTION	PHASE	RMS PHASE	CTRL	PACKAGE
NUMBER	(GHz)	BITS	LOSS (dB)	RANGE (°)	ERROR (°)	INTERFACE (V)	& STATUS
CGY 2172 XAUH/C1	8 - 12	6	8.00	360	2.00	0/-3	Die/Production
CGY 2172 XBUH/C1	8 - 12	6	8.00	360	2.00	0 / +5	Die/Production
CGY 2173 UH/C2	6 - 18	6	13.00	360	4.00	0 / -3	Die/Production
CGY 2174 UH/C1	13 - 16	6	8.00	360	6.00	0/-3	Die/Production
CGY 2177 AUH/C1	4.8 - 6.8		5.00	360	2.00	0/+5	Die/Production
CGY 2392 SHV/C1	6 - 18	6	10.80	360	1.90	0 / +5	QFN/Production
CGY 2392 SUH/C1	6 - 18	6	10.80	360	1.70	0 / +5	Die/Production

PERFORMANCE TABLE FOR DIGITAL ATTENUATORS FUNCTIONS							
PART NUMBER	FRQNCY (GHz)	CTRL BITS	INSERTION LOSS (dB)	ATTEN. RANGE (dB)	RMS ATTEN. ERROR (dB)	CTRL INTERFACE (V)	PACKAGE & STATUS
CGY 2169 UH/C1	8 - 12	6	4.00	24	0.40	0/-3	Die/Production
CGY 2171 XBUH/C1	1 - 12	6	5.00	32	0.25	0/+3	Die/Production
CGY 2176 UH/C1	4.8 - 6.8	6	5.60	32	0.20	0/+5	Die/Production
CGY 2191 SUH/C1	6 -18	6	4.00	32	0.20	0/+5	Die/Production
CGY 2390 SUH/C1	8 - 12	6	4.00	35	0.20	0/+5	Die/Production

S + ATT)										
RANGE B/°)	RMS ATTEN./PHASE ERROR (dB/°)	CTRL INTERFACE (V)	PACKAGE & STATUS							
/ 360	0.40/3.0	0/+3	QFN/Production							
/ 360	0.40/3.0	0/+3	Die/Production							
/ 360	0.35/3.0	0/+3	QFN/Production							
/ 360	0.30/3.0	0/+3	Die/Production							
/ 360	0.25/1.3	0/+5	Die/Production							
/ 360	0.20/1.3	0/+5	Die/Production							
/ 360	0.40/3.0	-3/3	Die/Production							
/ 360	0.35/4.0	0/+3	Die/Production							
/ 360	0.50/4.0	0/+5	Die/Production							

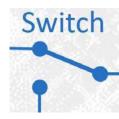
Mixers are manufactured using OMMIC's GaAs 180 nm E/D pHEMT (ED02AH) and 70 mm mHEMT (D007IH) technologies. They generally feature high isolation and can be used for application such as radar, telecommunication, instrumentation and GPS system.

PERFORMANCE TABLE FOR MIXERS										
PART NUMBER	2	FRQNCY (GHz)	LO FRQNCY (GHz)	IF FRQNCY (GHz)		CVRSN GAIN (dB)	ISO LO-RF (dB)	ISO LO-IF (dB)	IP1dB (dBM)	PACKAGE & STATUS
CGY 2180 U		0.7 - 3.7	0.7 - 4	DC - 2	15	-7	35	35	12	Die/Production
CGY 2180 0		1 - 4.5	1-5	DC - 2 DC - 2	15	-7		33	12	Die/Production
CGY 2181 01	,	3 - 10	3 - 10	DC - 3	15	-7	60	45	12	Die/Production
CGY 2183 U	'	0.1 - 6	0.1 - 6	DC - 3	-5	12	35	40	-5	Die/Production
CGY 2184 U		0.1 - 6	0.1 - 6	DC - 3	0	18	40	40	3	Die/Production
CGY 2460 U	H/C1	40,5 - 43,5	8.8 - 10	5.0 - 6	9	33			0	Die/Production
CGY 2470 U	H/C1	92 - 96	86 - 90	5.1 - 6	7	-3	4	3	2	Die/Production
CGY 2471 U	H/C1	92 - 96	86 - 90	5.2 - 6	7	-10		> 10	5	Die/Production

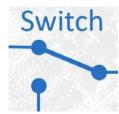
MISCELLANEOUS PORTFOLIO

OMMIC Portfolio of MMICs, includes up and down, passive and active converters, SPDT switches and diodes.

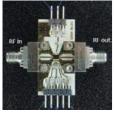
OTHER PRODUCTS



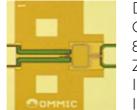
SPDT Switch : CGY**2890**SUH/C1 6-18 GHz Isolation : > 50 dB Insertion loss : 1,5 dB



SPDT Switch : CGY**2370**UH/C1 92-96 GHz Isolation : 20 dB Switching speed : 10 ns



Gain Block Taverny : CGY**2731**UH/C1 12-15 GHz Gain : 19 dB NF:4dB P3 dB : 10 dBm



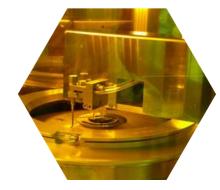
Detector diode : CGY**2870**AUH/C1 80-110 GHz Zero biais Input power : < 0 dBm Input matching : -15 dB

x8 Multiplier : CGY**2770**UH/C2 11-11,5 to 88-92 GHz Isolation : 20 dB Output power : 5 dBm



FOUNDRY SERVICES & III-V PROCESSES









FOUNDRY SERVICES III-V PROCESSES

EPITAXY

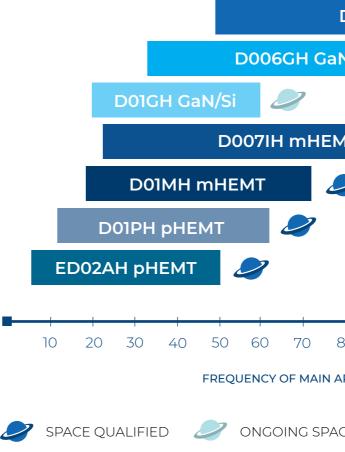
OMMIC has a powerful R&D department developing its own precesses starting from epitaxial structure. OMMIC has a number of MOCVD reactors and supply epi wafers in 3-inch, 4-inch and 6-inch.

This activity incluedes pHEMT containing up to 25% indium in the GalnAs layer, as opposed to 40% that they use internally, as well as HBT structures.





PROCESSES



III-V PROCESSES FOR FOUNDRY SERVICES

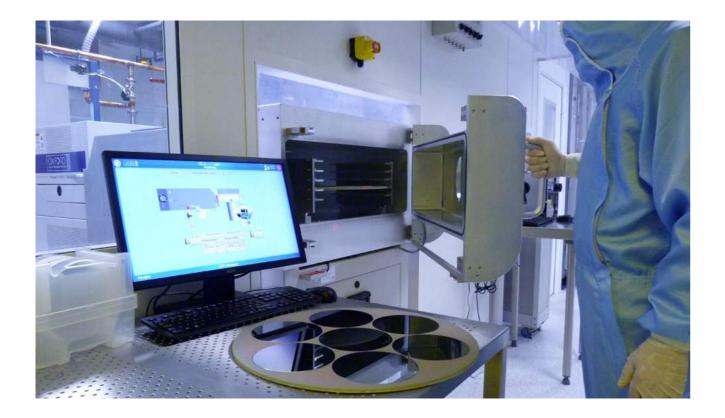
You have not found any corresponding design in our standart product porfolio? OMMIC as a fully open foundry policy, providing the most innovating processes to the rest of the world; use it to design the device that is best suited for you!

PROCESSES & TECHNOLOGY

OMMIC is focused on III-V material for the performance it can offers. Our process portolio includes GaAs pHEMT & mHEMT technology, InP HBT technology and GaN HEMT technology. These services enable cut-off frequencies as high as 400 GHz enabling new application at always higher frequencies.

OMMIC **processes** are built for high reliability and space application. This is why all our processes in production are either **spaced qualified** by the European Space Agency, or in the process of being qualified.

D004IH mHEMT				
N/Si	**			
١T	2			
2				
+ + +				
30 90 100	110 120 130 14	0		
PPLICATIONS (GHz)				
CE QUALIFICATION				



LOW NOISE APPLICATION

All of OMMIC processes are designed to minimize the noise figure of the transistors. Metamorphic technology (e.g D007IH, D004IH) is especially good for providing low noise at high frequencies.

Need for **robust LNA** (Pin > 40 dBm)?

The large Breakdown voltage combined with the low noise of our GaN (D01GH, D006GH) technologies makes it perfect for such feature.

POWER APPLICATION

The well-trusted reliability of GaAs pHEMT (D01PH) technology can be used for midpower application in space. For other environment, take advantage of the high power density of ou GaN processes (D01GH, D006GH). OMMIC's GaN technology features high output power (up to W-band), but also high linearity, low noise and no noiticeable memory effect.

Control Function :

With our ED02AH process, it is possible to have enhanced (E) and depletion (D) transistors on the same die. Having E- and D- type transistors allows one to design control functions with a serial interface that simplifies the interaction with the device.

GaN PROCESSES

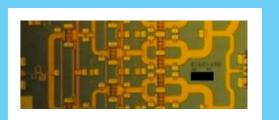
in Europe.

D01GH Process				
Technology Status Space Grade Gate Length Wafer Size Thinkness Gate Write Ft Fmax Vbgd Vds q Idss Idss max MIM Capacitors NF Power Density gm	GaN on Si Market Introduction in 2020 0.1 µm 3 inch / 6 inch 100 µm E-beam 110 GHz 160 GHz 36 V 12 V 1200 mA/mm 1700 mA/mm 400 pF/mm ² 1,5 dB (40 GHz) 3300 mW/mm CW 5,9 Pulse 800 mS/mm			

D006GH Process

Technology	GaN on Si
Status	Market Introduction
Space Grade	-
Gate Length	0,06 µm
Wafer Size	3 inch / 6 inch
Thinkness	100 µm
Gate Write	E-beam
Ft	150 GHz
Fmax	190 GHz
Vbgd	36 V
Vds q	12 V
Idss	1200 mA/mm
ldss max	1700 mA/mm
/IM Capacitors	400 pF/mm ²
NF	1 dB (40 GHz)
Power Density	3300 mW/mm CW 5,9 Pulse
gm	900 mS/mm

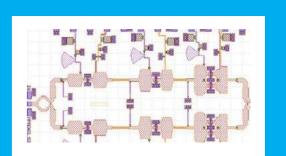
OMMIC has released its first GaN process in 2015. All of the supply chain is located



HPA ✓ ROBUST LNA ✓ T/R Chip ✓

Well suited for application from 15 to 50 GHz. CGY**2651**UH

Operating range : 37 GHz to 43 GHz Gain: 18 db **Pout :** 40 dBm @40 GHz **PAE:** 30% **Power Consumption :**



HPA 🗸 ROBUST LNA 🖌 SWITCH 🗸

Well suited for application from 50 to 100 GHz. Development Device : **Dev-WAVERIN**

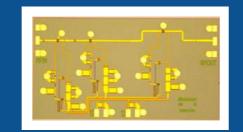


Operating range : 75 GHz to 89 GHz, CW Gain: 14 db **Pout :** 27 dBm @88 GHz **PAE:**10%

GaAs m-HEMT PROCESSES

OMMIC has released metamorphic processes with up to 70% of indium in the channel.

D007IH Process				
Technology Status Space Grade Gate Length Wafer Size Thinkness Gate Write Ft Fmax Vbgd Vds q Idss Idss max MIM Capacitors NF Power Density gm	GaAs m-Hemt Production Space Qualified 0,07 µm 3 inch 70 - 100 µm E-beam 300 GHz 450 GHz 4 V 3 V 200 mA/mm 400 mA/mm 400 pF/mm ² 0,5 dB (30 GHz) NA 1600 mS/mm	LNA Well s Repre CGY Opera Gain : NF 1.0 OP1dE Powe Vd = 1, Id = 0,		



NA 🗸 🛛 MIXER 🗸

Well suited for application from 20 to 150 GHz. Representative Device :

CGY**2260**UH/C1

Operating range : 25 GHz to 43 GHz **Gain :** 25 db (+ 0,4 db on bandwidth) **NF** 1.0 db @36 GHz **OP1dB :** 8 dBM **Power Consumption :** Vd = 1,5 V Id = 0,52 A

D00 Proc		
Technology Status Space Grade Gate Length Wafer Size Thinkness Gate Write Ft Fmax Vbgd Vds q Idss Idss max MIM Capacitors NF Power Density gm	GaAs m-Hemt Development - 0,04 µm 3 inch 100 µm E-beam 400 GHz 600 GHz 4 V 3 V 200 mA/mm 400 pF/mm ² 0,4 dB (30 GHz) NA 2000 mS/mm	LNA ✓ MIXER ✓ Well suited for application from 60 to 250 GHz.

D01MH Process

GaAs m-Hemt Production Space	
Qualified 0,07 µm 3 inch	LN
E-beam 150 GHz 250 GHz	We Rep CC
6 V 300 mA/mm 500 mA/mm	Op Gai NF
0,8 dB (30 GHz) 30 mW/mm 700 mS/mm	OP Pov Vd Id =
	Production Space Qualified 0,07 µm 3 inch 70-100 µm E-beam 150 GHz 250 GHz 8 V 6 V 300 mA/mm 500 mA/mm 400 pF/mm ² 0,8 dB (30 GHz) 30 mW/mm

GaAs p-HEMT PROCESSES

GaAs p-HEMT have been manufactured since the late nineties, whith a strong space heritage.

D01PH Process			
Technology Status Space Grade Gate Length Wafer Size Thinkness Gate Write Ft Fmax Vbgd Vds q Idss Idss max MIM Capacitors NF Power Density gm	GaAs p-Hemt Production Space Qualified 0,135 µm 3 inch 70 - 100 µm E-beam 100 GHz 180 GHz 12 V 10 V 500 mA/mm 400 pF/mm ² 1,1 dB (30 GHz) 640 mW/mm 650 mS/mm	PA We an Re C(Op Ga OF Po Vd Id	



ell suited for application from ? to ? GHz. epresentative Device : GY2128UH/C2

perating range : 24 to 34 GHz ain : 24 dB F : 1.3 dB PldB : 11 dBm ower Consumption : d =



0 GHz.

They are designing using OMMIC's PDK :

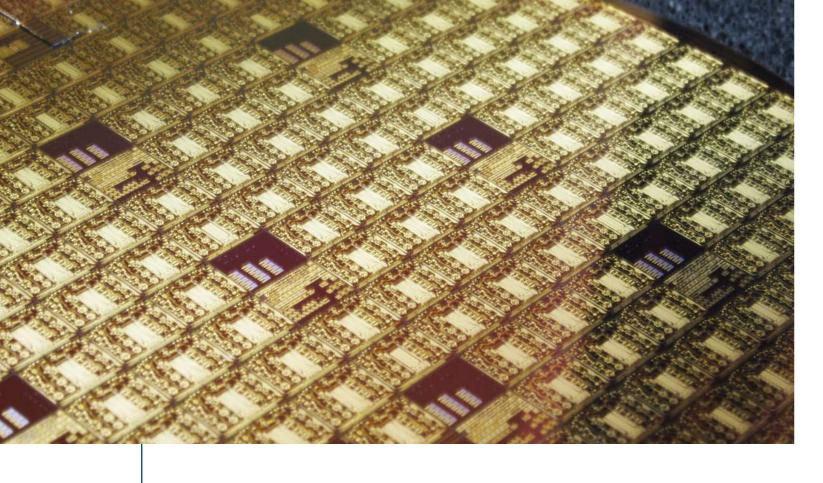




DESIGN KITS CUSTOM DESIGN ■ MPW SCHEDULE







DESIGN CENTER & FAB + SERVICES

DESIGN KITS

Having trouble finding a product with exotic specification on the market? Check-out other options!



based on customer's specifications, from DC to W-band.

Most of OMMIC's processes have completed or are running a space evaluation (ESA-EPPL). The OMMIC **design Manuals** and design tools are extremely comprehensive and allow any type of design. This includes mixed signal to low noise and high power, from DC to millimeter wave.

OMMIC design kits include :

- Fully scalable models for all devices
- Linear, non linear and noise models for transistors (and diodes)
 - representative yield analysis
 - Temperature effects for all passive and active devices

 - E.M. information allowing advanced analysis
- Electro-thermal simulator
- Design Rules Checking

Design kits are regularly updated on our website in close collaboration with software suppliers. OMMIC provides hot line support, dedicated training and powerful verification tools.

FOUNDRY SERVICE

All of OMMIC's processes are available for full wafer foundry services. This service comes with **on-wafer test** (following customer specification) and visual inspection (MIL-STD-883). Before manufacturing, all projects are checked by OMMIC using the OMMIC design rule checker (DRC). DRCs are performed at no extra cost.

A MultiProject Wafer (MPW) is a cost effective way to experience a new design topology or a new technology through a limited number of samples. OMMIC has been offering this service for a long time on his proprietary technologies.

Conditions of use :

- The size of the circuit must correspond to one of the fixed patterns for a MCP project.
- on the web site, by default 4 dates per year.
- MCP order should be placed at least 4 weeks before the annonced MCP start date.

University Partnership :

OMMIC is committed to give access to ts technologies for Educational Purposes to Universities and Educational Establishments. Please contact us for more details.

SIZES	1,5 mm	3 mm	
1 mm	A = 1,5 mm2 N = 25 Dies	A = 3 mm2 N = 20 Dies	A = Area of the N = Number of
2 mm	A = 3 mm2 N = 20 Dies	A = 6 mm2 N = 15 Dies	Other Die size used, please c special deman

Process statistical variations of all active and passive devices, allowing

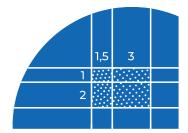
Complete auto layout for all devices, including all types of interconnections

■ The layout must be suplied according to a predefined time table available

The order needs to complain with minimum order value when it is applicable.

reticule. dies delivered.

can sometime be contact OMMIC for



CUSTOM DESIGN

OMMIC design team is able to design MMICs from Customer specifications and statement of Work.

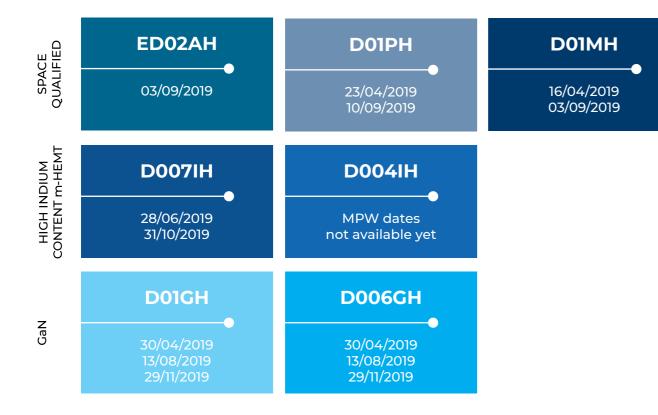
- LNA
- Power Amplifiers
- Multifunction chips including digital parts
- Multipliers
- Down-convertors or Trans Impedance Amplifiers from DC to W-band

The design flow includes several reviews whre close discussions with the customer ensure that the final MMIC will really enhances the final system.

This design flow based on space standards such as ECSS-Q60-12A and have been approved for flight model designs. The fabrication Line, Test Center, Reliability Center and Modeling Team are on the same site. This proximity allows OMMIC Design Center to obtain the best performances from all the OMMIC processes, while maintaining yield and reliability.

MPW SCHEDULE

Important date for available process for Multi Project Wafer (MPW).







For any other information or special request contact information@ommic.com Visit our website www.ommic.com for up-to-date information.





SPACE HERITAGE & FLIGHTS MODELS

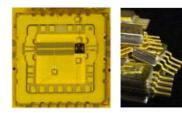
SPACE HERITAGE

More than 50 000 MMICs have been supplied for Flight Models. OMMIC has more than 1 000 000 years of accumulated Flight Life time around earth in several space mission and satellite equipment.

Components from OMMIC have been used in Flight Models for satellites from Europe, USA, India, Russia and other countries.

Functions include :

- Frequency Converters components as mixers and modulators
- Linear Components as Low Level Amplifiers, LNAs
- Control Components such as Medium Power Amplifiers
- Non Linear Components such as Frequencies Multipliers
- Negative Resistor for Oscillators
- Multi-functions components composed by several function
- Numerical Components as Phase or Frequency Detector



ESA has already evaluated 3 OMMIC processes : EDO2AH, D01PH and D01MH.These 3 processes being maintained on ESA EPPL list. Two additional processes are considered to be inserted in the EPPL list after ESA monitored evaluation procedures.

OMMIC has already delivered many standard parts designed during the ECI (European Component Iniative) programs. We can be a custom design center for space qualified components, many of them have already been designed by OMMIC's design team.

SPACE QUALIFICATION & RELIABILITY CENTER

OMMIC has a dedicated team for space gualification of flight models but also for reliability of all our components.

TEST PERFORMED FOR SPACE EVALUATION

All tests below are **assembly test** for flight models and are performed at OMMIC or specialised external laboratories.



They have already trusted OMMIC :



Jet Propulsion Laboratory California Institute of Technology







इसरी डिल्व

Together ahead. RUAG

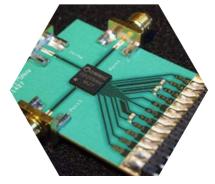




SALES **SUPPORT FIELD**

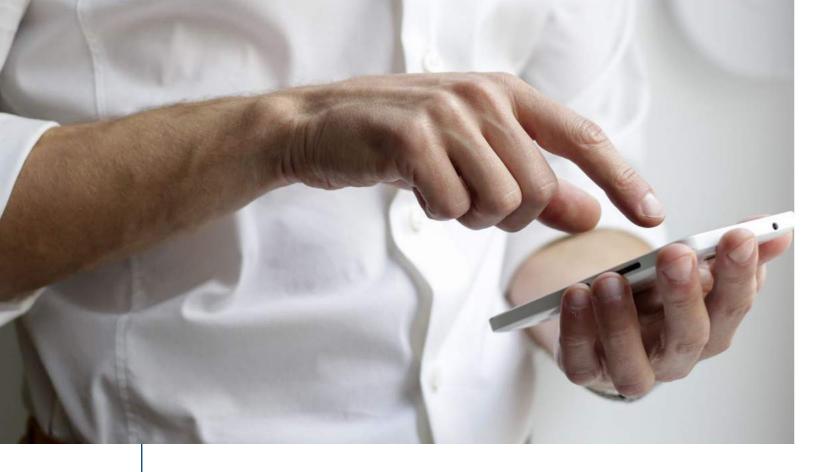
С

■ MMIC PACKAGING ■ SALES REPRESENTATIVE NETWORK ■ THEY TRUSTING US







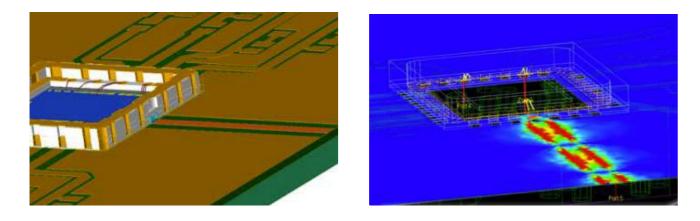


SALES SUPPORT FIELD

MMIC PACKAGING

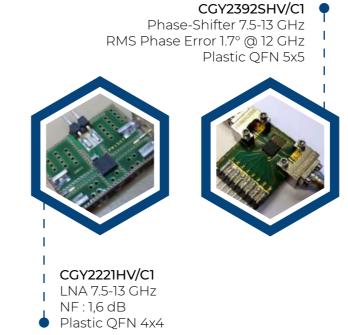
We are moving towards a word where integration and ease of use are central to the definition of complex electronic subsystems. OMMIC **invests every day** to simplify the use of its products for its customers by developing packaged solutions white ensuring optimal performances.

Exemple of modeling with EM simulation :



Today, our solutions cover L-, to Ka-band. This includes GaN products for power application, robust LNA and T/R chip front ends.

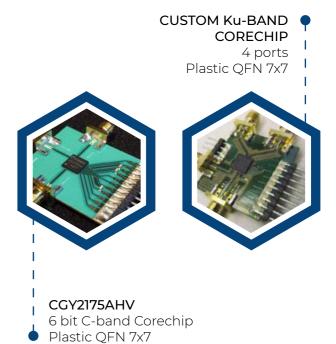
Exemple of LNA and Corechip packaged solution :



SALES REPRESENTATIVE NETWORK

A sales and field application team at OMMIC is dedicated to customer sales and **technical resquest** to provide the best support in the shortest time. Due to its world class status and human size, OMMIC is a very flexible company able to follow you in your most challenging projects. You can contact our support team whenever you need at : information@ommic.com Or meets us at international RF event such as IMS or EuMW!





Diversified

Based in France, in Paris area, OMMIC occupies a central position in Europe, but also in the world, to deliver the right product in the right time to customers. Thanks to its powerful supply chain and reactive regional reps network, OMMIC can support any project in the entire world.



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THEY TRUST US

More than 160 partners have already trusted OMMIC. Why not you ?





& more ...

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